

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : Ismail Kashkoush et al.
Serial No. : 10/585,229
Filed : April 20, 2007
Title: SYSTEM AND METHOD FOR SELECTIVE ETCHING OF SILICON
NITRIDE DURING SUBSTRATE PROCESSING
Art Unit : 1713
Examiner : Lan Vinh
Attorney Docket: : AKR-034-US
Confirmation No. : 9361

AMENDMENT UNDER 37 C.F.R. § 1.312 (ACCOMPANYING ISSUE FEE)

This Amendment is being submitted contemporaneously with the payment of the Issue Fee under 37 C.F.R. § 1.312. It is respectfully requested that the amendments set forth herein be accepted and entered in this case prior to issuance. The amendments are made to formalize the drawings. The amendments do not affect the allowed substance of the claim scope.

It is further requested that the subject application issue with the enclosed formal drawings.

Amendments to the Drawings begin on page 2 of this paper.

Remarks begin on page 3 of this paper.